

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)	ATTY. DOCKET NO. 60188-063	SERIAL NO.
	APPLICANT Bunji MIZUNO, et al.	
	FILING DATE April 24, 2001	GROUP

JC971 U.S. PTO
 09/840306

04/24/01

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO	DATE	NAME	CLASS	SUBCLASS	FILING DATE
AKS	5.085.885	2/4/1992	FOLEY et al.	—	—	
AKS	4.596.645	6/24/1986	STIRN	—	—	
AKS	5.320.984	6/14/1994	ZHANG et al.	—	—	
AKS	4.013.533	3/1977	COHEN-SOLAL et al.	—	—	
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AKS	5.672.541	9/1997	BOOSKE et al.	—	—	

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EXAMINER'S INITIALS	PATENT NO	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
AKS	01185918	7/25/1989	JAPAN	—	—		
AKS	5-24976	2/2/1993	JAPAN	—	—		
AKS	05343322	12/24/1993	JAPAN	—	—		
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AKS	40 02 269	8/2/1990	GERMANY	—	—		
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AKS	Johnson et al., "Solid-Source Doping of a-Si:H Thin Films Deposited with a remote Hydrogen Plasma", Journal of Non-Crystalline Solids 114, pp. 169-171 (December 1989)
	Mizuno et al., "New Methods for Ultra-Shallow Boron Doping by Using Plasma, Plasma-Less and Sputtering", International Conf. on Solid State Devices and Materials, pp. 1041-1042 (August 1995)
AKS	Cheung, "Plasma Immersion Ion Implantation for ULSI Processing", Nuclear Instruments & Methods In Physics Research. Section B: Beam Interactions with Materials and Atoms, Vol. B55, No. 1/4 (April 1991)
AKS	Gibilisco, "Encyclopedia of Electronics", TAB Professional and Reference Books, pp. 30-31 (1985)
AKS	K.C. Walter et al., Materials Research Bulletin, 29 (1994) 827
EXAMINER	DATE CONSIDERED
ASDle Murray Sarcher	3/19/02

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EXAMINER'S INITIALS	PATENT NO	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
AKS	0 771 020	5/2/1997	EUROPEAN	—	—		
	H54569	7/16/1997	CHINA				
	97-23693	5/30/1997	KOREA				
	346645	12/1/1998	TAIWAN				

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EXAMINER

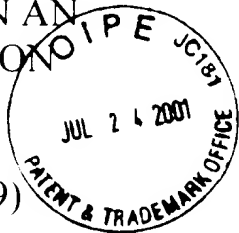
Assh Kumar Sarthar

DATE CONSIDERED

3/19/02

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AKS	3,461,054	8/12/69	Vratny			
AKS	3,732,158	5/8/73	Przybyszewski et al.			
AKS	4,108,751	8/22/78	King			
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						Yes	No
AKS	9-115851	2MAY97	JAPAN (Corres. USP 6,217,951)			X	

AKS	Greiner et al., "RF Sputtering Technique", IBM Technical Disclosure Bulletin, Vol. 17, No. 7, pp. 2172-2173					

EXAMINER Asok Kumar Saxhar	DATE CONSIDERED 3/19/02
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EXAMINER Initial if reference considered, whether or not citation is in conformance with MPEP 609, draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.